

Figure 3A- Pure tungsten microstructure (400x).

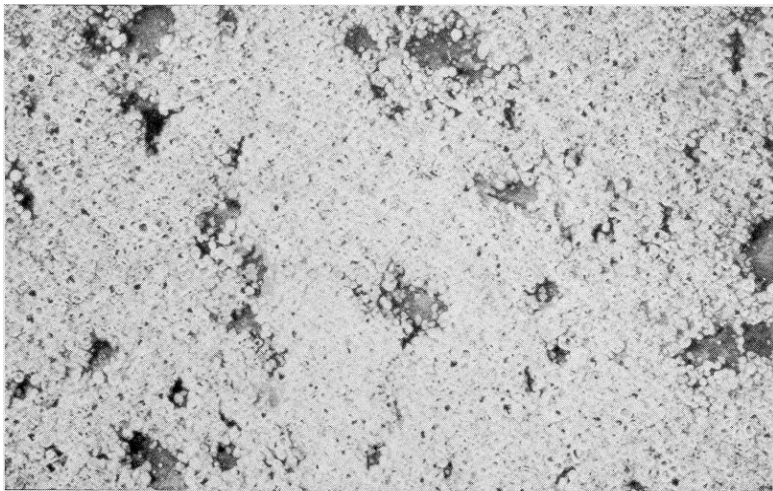


Figure 3B- W 10%Ti, etched (200x).

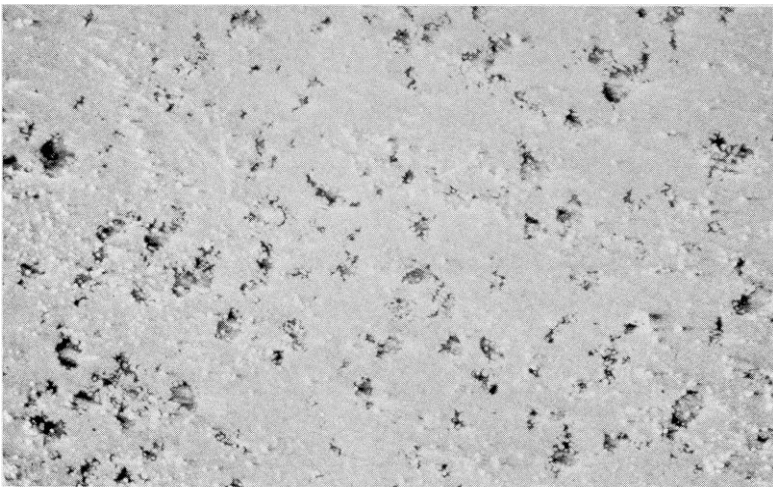


Figure 3C- W 10% Ti, polished (100x).

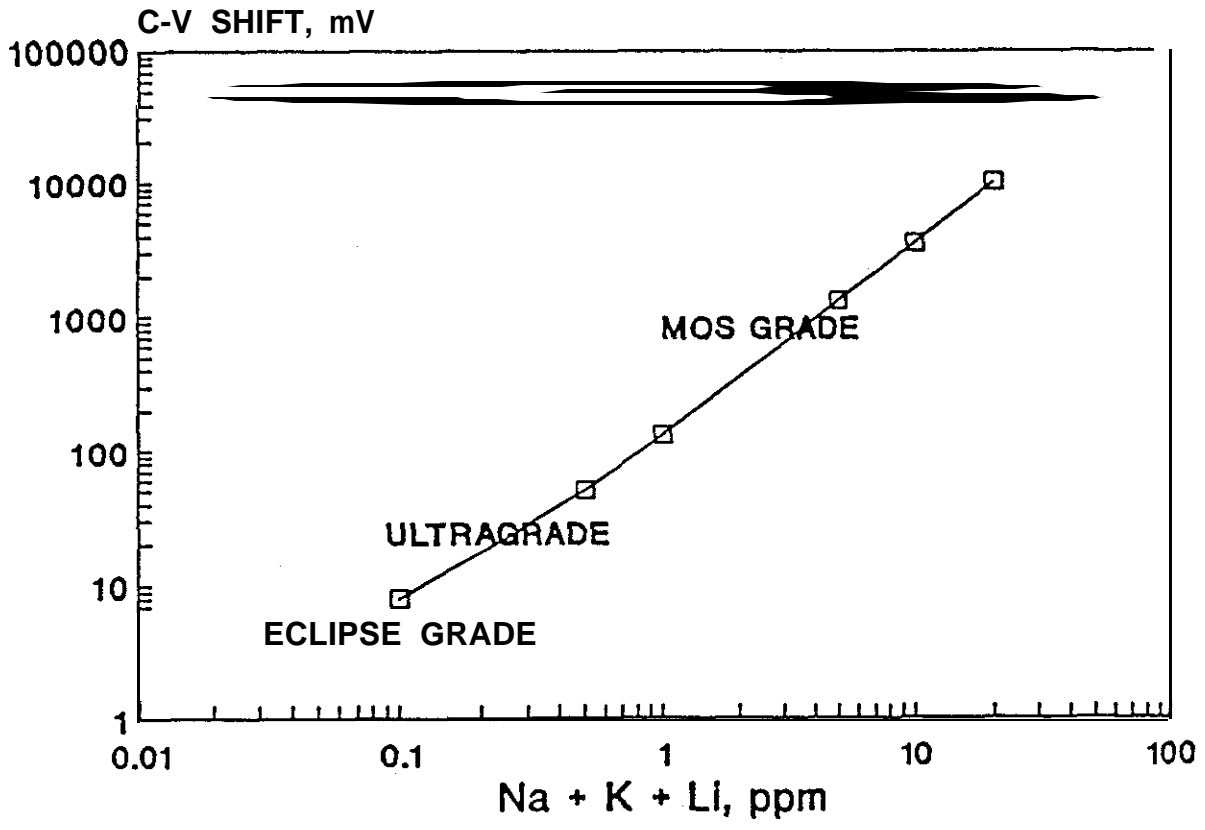


Figure 4- Target alkali content vs. C-V shift.

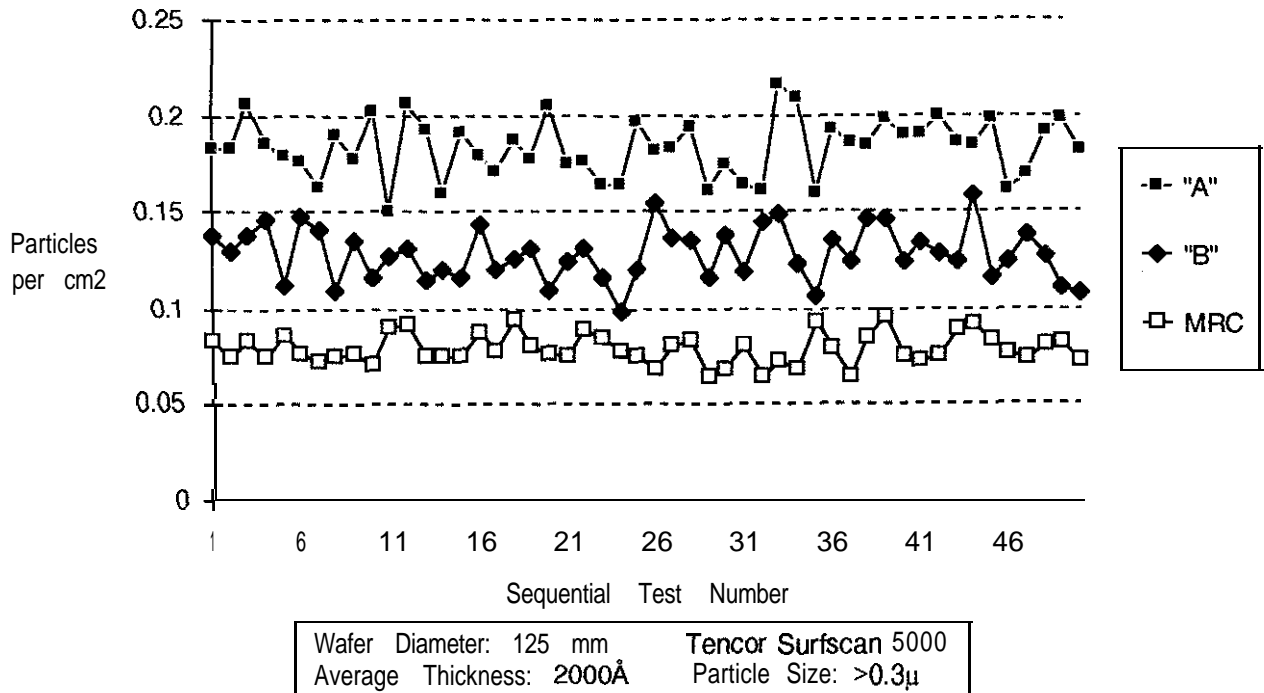


Figure 5- WII particulate generation data.

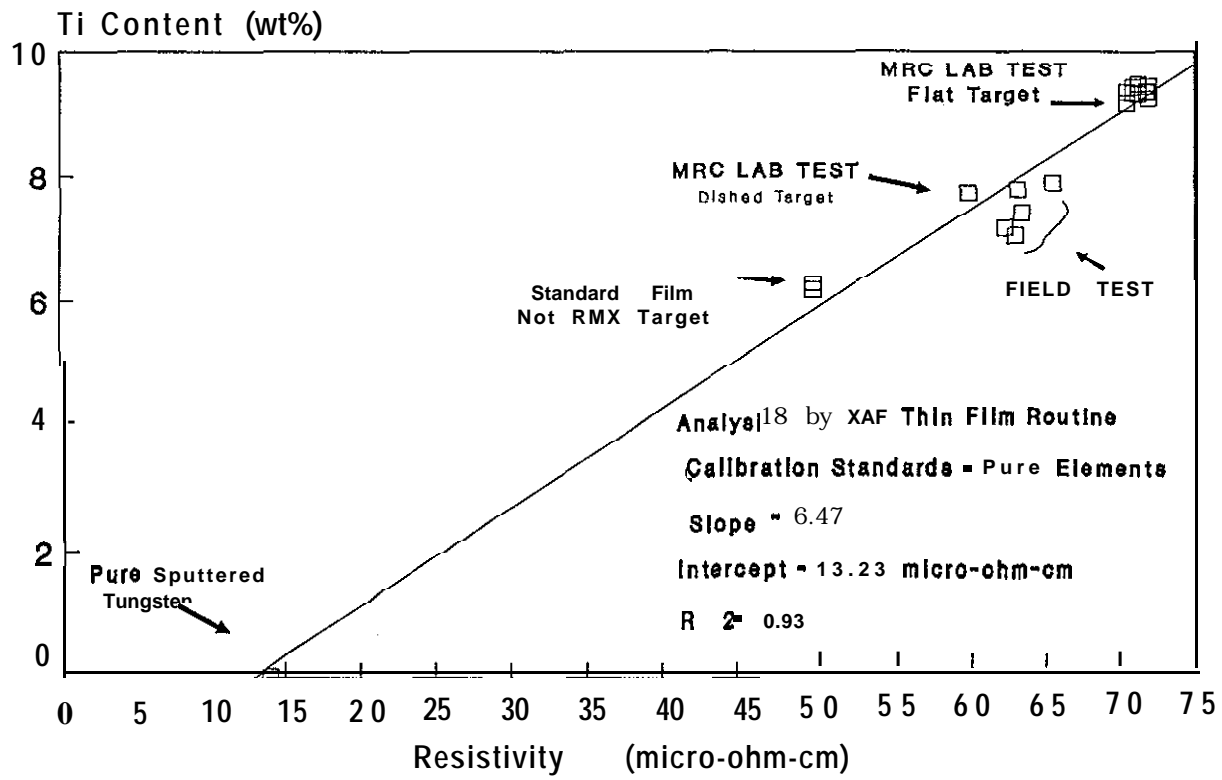


Figure 6- Film titanium content vs. resistivity.  
 (Target titanium content 10 %)

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